

IN THE CLAIMS

The following listing of claims will replace the listing of claims in the parent application. Attention is drawn to insertions and deletions by showing these in bold face.

1-11. (Canceled)

12. (Currently amended) A matrix for transdermal administering of rotigotine, **comprising** **containing** a matrix polymer supersaturated with rotigotine base, wherein a portion of the rotigotine not dissolved in the matrix polymer is dispersed in the matrix polymer as **amorphous** ~~amphorous~~ particles with a maximum mean diameter of 30 μm , and the matrix is free of solvents, crystallization inhibitors and dispersants.
13. (Currently amended) A matrix for transdermal administering of rotigotine, consisting of:
- (a) matrix polymer,
 - (b) rotigotine base in a concentration above the solubility limit of the matrix polymer, wherein a portion of the rotigotine not dissolved in the matrix polymer is dispersed in ~~the~~ matrix polymer as **amorphous** ~~amphorous~~ particles with a maximum mean diameter of 30 μm , and
 - (c) optionally one or more antioxidants.
14. (Currently amended) **The matrix of** ~~A matrix according to~~ claim 12 or 13 wherein the matrix polymer is an **amine-resistant silicone** ~~amino-resistant silicon~~ or a mixture of **amine-resistant silicones** ~~amino-resistant silicones~~.
15. (Currently amended) **The matrix of** ~~A matrix according to~~ claim 12 or 13 wherein the matrix is self-adhesive.
16. (Currently amended) **The matrix of** ~~A matrix according to~~ claim 12 or 13 wherein the matrix consists of:
- (a) about 60 to about 95 weight percent of an **amine-resistant silicone** ~~amino-resistant silicon~~ or an **amine-resistant silicone** ~~amino-resistant silicon~~ mixture,
 - (b) about 5 to about 40 weight percent amorphous rotigotine base dispersed in the **silicone**, ~~silicon~~ and

(c) 0 to about 2 weight percent antioxidant.

17. (Previously presented) A system for transdermal administering of rotigotine comprising a matrix of claims 12 or 13 and a backing.
18. (Previously presented) The system of claim 17 wherein the backing is impermeable to rotigotine.
19. (Previously presented) The system of claim 17 wherein the rotigotine charge is between 0.3 to 6 mg/cm³.
20. (Previously presented) A method for treating a patient suffering from or susceptible to Morbus Parkinson comprising administering rotigotine to the patient with a matrix of claim 12 or 13.
21. (Previously presented) The method of claim 20 wherein the patient has been identified as suffering from Morbus Parkinson and rotigotine is administered to the identified patient.
22. (Previously presented) A method for treating a patient suffering from or susceptible to Restless Leg Syndrome comprising administering rotigotine to the patient with a matrix of claim 12 or 13.
23. (Currently amended) The method of claim 22 [20] wherein the patient has been identified as suffering from Restless Leg Syndrome and rotigotine is administered to the identified patient.
24. (Previously presented) A method for treating a patient suffering from or susceptible to depression comprising administering rotigotine to the patient with a matrix of claim 12 or 13.
25. (Previously presented) The method of claim 24 wherein the patient has been identified as suffering from depression and rotigotine is administered to the identified patient.
26. (Currently amended) A method for producing a pharmaceutical matrix for transdermal administering of rotigotine, comprising:
 - (a) dissolving matrix polymer in one or more solvents;

- (b) adding rotigotine base in crystalline form in a quantity above the solubility limit of the matrix polymer;
 - (c) removing solvent and heating the matrix produced in (b) to at least about 74°C for a time sufficient to melt rotigotine; and
 - (c) cooling the matrix.
27. (Previously presented) The method of claim 26 wherein the rotigotine polymer matrix produced in (b) is applied on a substrate impermeable to rotigotine.
28. (Previously presented) The method of claim 27 wherein after applying the rotigotine polymer matrix on the substrate solvent is removed.